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## (54) WASTE LIQUID-FREE POST-TREATMENT OF CHLOROSILANE DISTILLATION RESIDUE

(57)Abstract:

**PURPOSE:** To economically treat a chlorosilane distillation residue free from a waste liq. by allowing the chlorosilane distillation residue generated in the production of chlorosilane by the reaction of silicon with chlorine to react with a specified excess of calcium base or calcium carbonate over stoichiometry in a water phase.

**CONSTITUTION:** The chlorosilane distillation residue is post-treated without forming a waste liq. by the reaction with calcium base or calcium carbonate in a water phase. In this case, an excess of at least 15% of calcium base or calcium carbonate over stoichiometry is used, the solid generated by the reaction is separated (e.g. filtration and centrifugal separation from the reaction mixture, and the remaining reaction mixture is recycled into the process. In this method, the separated wetted solid is wholly or partly dried, and the moisture removed by the drying is preferably returned to the process.